

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Atty. Docket

WALTER J.A. DE COSTER ET AL

PHQ 99,010

Serial No.

Filed: CONCURRENTLY

METHOD OF MANUFACTURING AN INTEGRATED CIRCUIT COMPRISING AN
IMPROVED SILICIDATION AND A CORRESPONDING INTEGRATED CIRCUITHonorable Commissioner of Patents and Trademarks
Washington, D.C. 20231PRELIMINARY AMENDMENT

Sir:

Prior to calculation of the filing fee and examination,
please amend the above-identified application as follows:

IN THE CLAIMS

Please amend the claims as follows:

3. (Amended) A method as claimed in claim 1, characterized in
that the depth (h) of the trench is equal to maximally half the
height (H1) of the larger isolation layer and maximally half the
thickness (E) of the larger isolation layer.

4. (Amended) A method as claimed in claim 1, characterized in
that
the vertical portion of the smaller isolation layer (402) is
anisotropically etched.